

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

OFFICIAL

Applicant: Gautam V. Thakar, et al.

Art Unit: 2812

Serial No.: 10/645,032

Examiner: Walter L. Lindsay, Jr.

Filed: 08/21/03

Docket: T1-32822.1

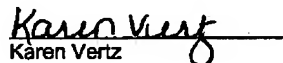
For: Polysilicon Processing Using an Anti-Reflective Dual Layer Hardmask for
193 nm Lithography

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

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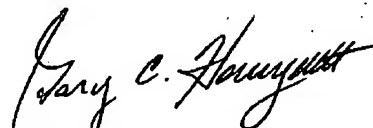
ELECTION

This election is offered in response to the Examiner's restriction requirement
mailed April 23, 2004.

Applicants hereby provisionally elect to pursue the first invention with Claims 19-
21, drawn to an anti-reflective coating, classified in class 257, subclass 1+.

Respectfully submitted,

Texas Instruments Incorporated
P.O. Box 655474, M/S 3999
Dallas, TX 75265
(972) 470-0130



Gary C. Honeycutt
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In re the Application of

Applicant Gautam V. Thakar, et al.

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NAME OF INVENTOR(S): Gautam V. Thakar, et al.	
TITLE OF INVENTION: Polysilicon Processing Using an Anti-Reflective Dual Layer Hardmask for 193 nm Lithography	
TI FILE NO.: TI-32822.1	DEPOSIT ACCT. NO.: 20-0668
RECEIPT DATE & SERIAL NO.: Serial No.: 10/645,032 Filing Date: 08/21/03	
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